Preface

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The 2012 OPU-KIST-ECUST Joint Symposium on Advanced Materials and their Applications (JSAMA2012) was held in Osaka Prefecture University (OPU, Sakai, Japan) on September 10th–11th, 2012. The “2011 KIST-OPU Joint Symposium on Nano-Science and Materials” was first held on May 2nd–3rd, 2011, at the Korea Institute of Science and Technology (KIST, Seoul, South Korea), to promote scientific cooperation between KIST and OPU. In JSAMA2012, the scientific cooperative relationship was expanded to involve three organizations, OPU, KIST, and the East China University of Science Technology (ECUST, Shanghai, China). The JSAMA2012 conference provided a forum for international colleagues to exchange innovative ideas on scientific findings and technological developments in the field of advanced materials. The key topics of the conference were:

- 1 environment-related materials;
- 2 nano-ordered catalysts and photocatalysts;
- 3 nano-structured and/or hybrid materials;
- 4 energy related materials; and
- 5 biomaterials.

This special Issue of Research on Chemical Intermediates contains manuscripts presented at JSAMA2012. The purpose of the symposium was to give an overview of the present status of the topic and to foresee future trends in the field of advanced materials. The symposium was composed two plenary lectures, 15 invited talks, and

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Fig. 1 Group photograph of the participants in JSAMA 2012 held at Osaka Prefecture University (Sakai, Japan) on September 10th–11th, 2012

30 poster presentations. Only 13 selected and extended papers were accepted and revised; these are published in this special issue.

This symposium provided a good chance for scientists to communicate and exchange new ideas about science and technology and recent scientific findings and technological developments with one another. We would like to express our sincere gratitude to all of the members of the Organizing Committee, and the lecturers. Finally, we would also like to thank all the authors who submitted their manuscripts and revisions and all the reviewers who spent much time reviewing and commenting. We hope this special issue will be accepted as an original and valuable contribution to the literature in the field of advanced materials (Fig. 1)